



JFW

**PATENT APPLICATION**

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re application of

Docket No: Q77760

OGATA, TOSHIYUKI, et al.

Appln. No.: 10/748,190

Group Art Unit: 1752

Confirmation No.: 5536

Examiner: Not yet assigned.

Filed: December 31, 2003

For: POSITIVE RESIST COMPOSITION AND BASE MATERIAL CARRYING LAYER OF  
THE POSITIVE RESIST COMPOSITION

**PRELIMINARY AMENDMENT**

**MAIL STOP AMENDMENT**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

Prior to examination, please amend the above-identified application as follows on the  
accompanying pages.

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